

L Number	Hits	Search Text	DB	Time stamp
1	1582	(hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	USPAT; US-PGPUB	2003/02/12 14:02
18	299	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (resist pr photo?resist (photo near2 resist))	USPAT; US-PGPUB	2003/02/12 13:40
19	47	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (resist pr photo?resist (photo near2 resist))) and (spin near5 coat\$3)	USPAT; US-PGPUB	2003/02/12 13:36
20	807	(hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	EPO; JPO; DERWENT; IBM TDB	2003/02/12 14:01
21	10	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (resist pr photo?resist (photo near2 resist))	EPO; JPO; DERWENT; IBM TDB	2003/02/12 13:40
22	23244	(spin?coat\$3 (spin adj2 coat\$3))	USPAT; US-PGPUB	2003/02/12 13:58
23	10431	((spin?coat\$3 (spin adj2 coat\$3))) and (photo?resist resist PR)	USPAT; US-PGPUB	2003/02/12 13:59
24	8025	((spin?coat\$3 (spin adj2 coat\$3))) and (photo?resist resist PR)) and (trench via hole open\$4 recess)	USPAT; US-PGPUB	2003/02/12 14:00
26	2635	((spin?coat\$3 (spin adj2 coat\$3))) and (photo?resist resist PR)) and (trench via hole open\$4 recess)) and (CMP planar\$6)	USPAT; US-PGPUB	2003/02/12 14:01
29	25	((spin?coat\$3 (spin adj2 coat\$3))) and (photo?resist resist PR)) and (trench via hole open\$4 recess)) and (CMP planar\$6) ) and (hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	USPAT; US-PGPUB	2003/02/12 14:02

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5	1582	(hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	USPAT; US-PGPUB	2003/02/12 16:40
6	188	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and ((shallow near3 trench) STI)	USPAT; US-PGPUB	2003/02/12 16:30
7	0	((("6146968").PN.) and STI	USPAT; US-PGPUB	2003/02/12 16:30
8	0	((("6146968").PN.) and ((shallow near3 trench) STI)	USPAT; US-PGPUB	2003/02/12 16:30
9	220	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (dual damascene)	USPAT; US-PGPUB	2003/02/12 16:53
10	202446	(dual damascene)	USPAT	2003/02/12 16:53
12	1561	(dual near2 damascene)	USPAT	2003/02/12 16:55
-	16976	(spin?coat\$3 (spin adj2 coat\$3))	USPAT; US-PGPUB	2002/02/13 18:47
-	190792	photoresist resist	USPAT; US-PGPUB	2002/02/13 18:47
-	2089185	trench via hole open\$4 recess	USPAT; US-PGPUB	2002/02/13 18:48
-	7027	((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)	USPAT; US-PGPUB	2002/02/13 17:13
-	3842	((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)	USPAT; US-PGPUB	2002/02/13 17:14
-	295	((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)) and (first with speed)	USPAT; US-PGPUB	2002/02/13 17:15
-	511	((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)) and (second with speed)	USPAT; US-PGPUB	2002/02/13 17:15
-	63	((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)) and (third with speed)	USPAT; US-PGPUB	2002/02/13 17:15
-	33	((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)) and (first with speed)) and (((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)) and (second with speed)) and (((spin?coat\$3 (spin adj2 coat\$3))) and (photoresist resist) and (trench via hole open\$4 recess)) and (speed rpm)) and (third with speed))	USPAT; US-PGPUB	2002/02/13 18:05
-	96	(spin?coat\$3 (spin adj2 coat\$3))	USOCR	2002/02/13 18:47
-	151723	photoresist resist	USOCR	2002/02/13 18:47
-	1582	(hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	USPAT; US-PGPUB	2003/02/12 14:02
-	299	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (resist pr photo?resist (photo near2 resist))	USPAT; US-PGPUB	2003/02/12 13:40
-	47	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (resist pr photo?resist (photo near2 resist))) and (spin near5 coat\$3)	USPAT; US-PGPUB	2003/02/12 13:36
-	807	(hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	EPO; JPO; DERWENT; IBM_TDB	2003/02/12 14:01
-	10	((hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))) and (resist pr photo?resist (photo near2 resist))	EPO; JPO; DERWENT; IBM_TDB	2003/02/12 13:40
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-	25	((spin?coat\$3 (spin adj2 coat\$3))) and (photo?resist resist PR) and (trench via hole open\$4 recess)) and (CMP planar\$6) ) and (hsg (hemispherical near5 silicon) hsg?si (hemi near10 silicon))	USPAT; US-PGPUB	2003/02/12 14:03